Abstract

In a device (20) for chemical wet treatment of substrates (25) in a tank (21) containing a treatment fluid (23), comprising a lifting apparatus for introducing and removing at least one substrate carrier (17) and the substrates (25), a continuous removal and introduction is achieved by providing the lifting apparatus with a first transport carriage for the substrates (25) and a second transport carriage for the substrate carrier (17).

(Fig. 3)